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PATENT & TRADEMARK OFFICE

2818

PATENT

Atty. Dkt. No. AMAT/6392/DSM/LOW K/JW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#74 Andt
M. Brunson
5/2/03

In re Application of:
Xia, et al.

Serial No.: 10/010,950

Confirmation No.: 5694

Filed: November 13, 2001

For: A Method of Depositing Low K Barrier Layers

Group Art Unit: 2818

Examiner: Dung Anh Le

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CERTIFICATE OF MAILING
37 CFR 1.8
I hereby certify that this correspondence is being deposited on April 30, 2003, with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231.

4/30/03
Date

Signature

Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

RESPONSE TO OFFICE ACTION DATED JANUARY 30, 2003

In response to the Office Action dated January 30, 2003, having a shortened statutory period for response set to expire on April 30, 2003, please enter this response and reconsider the claims pending in the application for reasons discussed below. The Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/6392/KMT, for $36.00 for two additional claims, and any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

IN THE SPECIFICATION:

Please replace paragraph **[0019]** with the following paragraph:

[0019] It was unexpectedly and surprising discovered by the inventors herein that depositing silicon carbide materials with an organosilicon compound having the formula $SiH_a(CH_3)_b(C_6H_5)_c$, wherein a is 0 to 3, b is 0 to 3, and c is 1 to 4, under the processing

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